

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Masashi UEDA et al.

Application No.: 09/830,879

Filed: May 2, 2001



Group Art Unit: 1763

Examiner: P. Hassanzadeh

Docket No.: 109426

12A

3/26/03
MWFor: INTERNAL ELECTRODE TYPE PLASMA PROCESSING APPARATUS AND
PLASMA PROCESSING METHODAMENDMENT UNDER 37 C.F.R. §1.111Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231RECEIVED
MAR 25 2003
TC 1700

Sir:

In reply to the December 24, 2002 Office Action, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Page 17, lines 3-20, delete current paragraph and insert therefor:

A₁

In other words, the shape and dimensions of the electrode 12 is designed and the frequency of the high frequency power supplied to the electrode 12 is determined so that the standing waves are positively created having, for example, one antinode at each of the two parallel straight portions of the electrode 12. Further, when supplying the high frequency power from the high frequency power generator 13 to the U-shaped electrode 12, one end 12b is made to be the feeding point and the other end 12c is connected to the ground. By doing this, the standing wave of one wavelength is generated on the electrode 12 with controlled standing waves generated at the two straight portions of the electrode 12. In the standing waves of the half wavelength generated at each of the two straight portions of the U-shaped